

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

M. KOZAWA et al.

Group Art Unit: 1712
(expected)

Serial Number: Divisional of
09/553,479

Examiner: K. Peng
(expected)

Filed: December 7, 2001

Atty. Docket No.: 100021-00065

For: SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,
RESIST COMPOSITION EMPLOYING IT, PATTERN-FORMING METHOD
AND ELECTRONIC DEVICE FABRICATION METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
Washington, D.C. 20231

Date: December 7, 2001

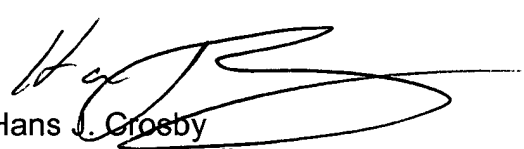
Sir:

In consideration of Applicants' duty of disclosure under 37 C.F.R. §1.56 and 37 C.F.R. §1.97, Applicants wish to bring to the Examiner's attention the documents cited in the parent application, U.S. Serial No. 09/553,479, which are listed on the attached Form PTO-1449. Pursuant to 37 C.F.R. §1.98(d) and M.P.E.P. §609, copies of these documents are not provided.

In the event any fees are required with respect to this paper, please charge our Deposit Account No. 01-2300.

Respectfully submitted,

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Enclosure: PTO-1449

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